

Serial No. 09/745,350Docket No. 27710-ARemarks:

Claims 1-14, 16-26, 28-30, and 83 remain for consideration in this application. Claims 1 and 19 have been amended.

It is noted with appreciation that the Examiner withdrew the 35 U.S.C. § 112, second paragraph rejections and the 35 U.S.C. § 103 rejection based on Eissa in view of Butterfield and Nichols in view of NN73101442. Furthermore, although not explicitly stated in the office action, the Examiner has dropped the rejection of claims 1-18 as being anticipated by U.S. Patent No. 5,991,081 to Haaland.

The Examiner did, however, reject claims 19, 21-23, 25, and 28-29 as being anticipated by the Haaland patent. Claim 19 is the only independent claim subject to this rejection. It is the applicants' understanding that the Examiner maintained this rejection because she is treating this claim as a product-by-process claim, so patentable weight is not being given to the recited structural formula. Claim 19 has been amended to recite the structure of the polymer that is polymerized and deposited on the surface of the substrate. Support for this amendment can be found throughout the specification, including at page 4, lines 10 et seq. and page 7, lines 6-13. With this limitation, the chemical structure of the polymer as it exists on the substrate surface is clearly a part of this claim so this claim is patentable over the Haaland patent because there is no teaching or suggestion of this structure in the Haaland patent.

The Examiner rejected claims 1-15, 16-26, and 28-30 as being obvious in view of JP 8-064492. Claim 1 has been amended to overcome this rejection. Specifically, claim 1 now recites that each R is individually selected from the group consisting of alkyl groups. This limitation

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is not taught or suggested by the JP 8-064492 reference. Rather, the JP 8-064492 reference teaches the use of C=N groups as the linkage groups. The claimed R groups are important because their presence allows for more rapid and facile deposition of the anti-reflective layer than that attained in the prior art.

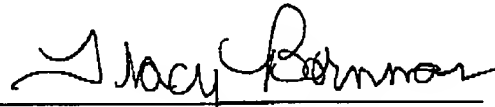
New claim 83 corresponds to claim 1 as it stood prior to this amendment except that the possible X groups have been amended to exclude halogens. This is also different than the JP 8-064492 reference, which clearly teaches the use of halogens (and particularly fluorine atoms). Thus, claim 83 now recites that "each X is individually selected from the group consisting of hydrogen, nitro groups, amino groups, acetamido groups, substituted and unsubstituted cyclic and heterocyclic groups, and COR¹, where R¹ is selected from the group consisting of hydrogen, substituted and unsubstituted phenyl groups, substituted and unsubstituted alkyl groups, cinnamoyl, naphthoyl, acryloyl, methacryloyl, furoyl, and thiophenecarbonyl groups." This limitation is not taught or suggested by the JP 8-064492 reference, either alone or when considered with the art of record. It is respectfully submitted that all rejections predicated upon the JP 8-064492 reference should now be withdrawn.

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It is believed that no further issues remain in this patent application. In view of the foregoing amendments, it is believed that the pending claims are in condition for allowance, and a Notice of Allowance is respectfully requested. Any additional fee which is due in connection with this amendment should be applied against our Deposit Account No. 19-0522.

Respectfully submitted,

By



Tracy Bornman, Reg. No. 42,347
HOVEY WILLIAMS LLP
2405 Grand Boulevard, Suite 400
Kansas City, Missouri 64108
816/474-9050

ATTORNEYS FOR APPLICANT(S)